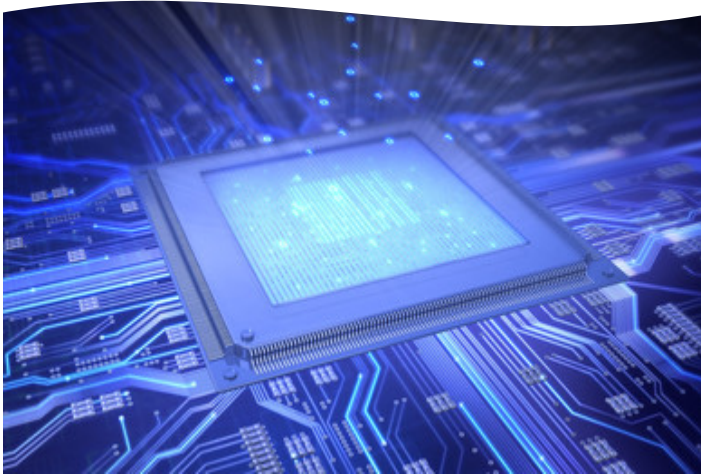


# <sup>11</sup>B in the Form of Boron Trifluoride Gas for Semiconductor Manufacture



Boron trifluoride gas is the ideal silicon wafer dopant for the production of highly integrated, high-density microchips.  $^{11}\text{BF}_3$  provides for greater efficiency and increased production throughput, and helps to make chips smaller and better.

# <sup>11</sup>B in the Form of <sup>11</sup>BF<sub>3</sub> Gas

## Specification

### Physical properties:

- Material <sup>11</sup>B – Boron-11 in the form of Boron Trifluoride Electronic Grade
- Enrichment <sup>11</sup>B > 99,9at%

### Chemical Properties:

- Form BF<sub>3</sub>
- Purity > 99,99wt%

## Impurities in vppm

Ar	≤ 25
O <sub>2</sub>	≤ 25
CO <sub>2</sub>	≤ 25
HF	≤ 25
N <sub>2</sub>	≤ 25
SiF <sub>4</sub>	≤ 25
SO <sub>2</sub>	≤ 25

Our gas is fully compatible with VLIS-requirements.

## NUKEM Isotopes GmbH

Rodenbacher Str. 47, 63755 Alzenau, Germany, T: +49 (0)6023 9474-800, F: +49 (0)6023 9474-813  
E: [info@nukemisotopes.de](mailto:info@nukemisotopes.de), I: [www.nukem-isotopes.com](http://www.nukem-isotopes.com)